Application No. 09/295,607 Docket No. 740756-1961

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

His Patent Application of:		
Patent Application of:	)	
Shunpei YAMAZAKI et al.	)	Examiner: Steven Ho Yin Loke
Serial No. 09/295,607	)	Group Art Unit: 2811
Filed: April 22, 1999	)	
For: SEMICONDUCTOR DEVICE HAVING	)	
ALUMINUM NITRIDE FILM	)	Confirmation No. 7371

## CERTIFICATE OF MAILING OR TRANSMISSION

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage for First Class Mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on December 31,2003.

Signature: North All Malinativame. The Words head in

## INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450 XECEIVED JAN - 7 2004 DI GGY CENTER 2800

Sir:

In accordance with the duty of disclosure as set forth in 37 C.F.R. §1.56, Applicants hereby submit the following information in conformance with 37 C.F.R. §§ 1.97 and 1.98. Pursuant to 37 C.F.R. § 1.98, a copy of each of the documents cited is enclosed.

The documents are being submitted before the first Office Action on the merits, therefore no fee or certification is required under 37 C.F.R. § 1.97(b).

Applicants note that U.S. Patent No. 5,192,644 and U.S. Patent No. 4,832,986 are cited for disclosing an AlN film. Further, the JP 03-175632 and HSIEH, J.J., et al., "DIRECTIONAL DEPOSITION OF DIELECTRIC SILICON OXIDE BY PLASMA ENHANCED TEOS PROCESS" references were cited in a family application Serial No. 09/432,106, and the JP 58-085520, JP 62-214669, JP 02-033935, and JP 04-139727 references were cited in a counterpart Japanese patent application which were made available to Applicants on October 28, 2003.

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It is requested that the accompanying PTO-1449 be considered and made of record in the above-identified application. To assist the Examiner, the documents are listed on the attached form PTO-1449. It is respectfully requested that an Examiner initialed copy of this form be returned to the undersigned.

The Commissioner is hereby authorized to charge any fees connected with this filing which may be required now, or credit any overpayment to Deposit Account No. 19-2380. (740756-1961)

Respectfully submitted,

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Complete if Known 09/295,607 Application Number INFORMATION DISCLOSURE Filing Date April 22, 1999 STATEMENT BY APPLICANT Shunpei YAMAZAKI First Named Inventor (use as many sheets as necessary) Art Unit Steven Ho Yin Loke Examiner Name of 1 Attorney Docket Number 740756-1961

U.S. PATENT DOCUMENTS						
Examiner Initials	Cite No.'	U.S. Patent Document  Number - Kind Code <sup>3</sup> (If Intown)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	
		US-4,832,986	05-23-1989	Gladfelter et al.		
		US-5,192,644	03-09-1993	Ohta et al.		
	1					

			DREIGN PATENT D			
Examiner Initials	Cite No.1	Foreign Patent Document  Kind Code <sup>5</sup> Country Code <sup>5</sup> Number <sup>4</sup> (If known)	Publication Date MM-DD-YYYY	Name of Patentee Application of Cited Do		T <sup>6</sup>
	+	JP 58-085520	05-21-1983	Koba		Abstract
		JP 62-214669	09-21-1987	Kaneko et al.		Abstract
		JP 02-033935	02-05-1990	Yazaki		Abstract
		JP 03-175632	07-30-1991	Fujiki et al.		Abstract
_	$\top$	JP 04-139727	05-13-1992	Matsumoto et a	ıl.	Abstract
		OTHER PRIOR	ART – NON PATENT I	ITERATURE DOCUM	ENTS	
Examiner Initials	Cite No.1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.				
HSIEH, J.J., ET AL., "DIRECTIONAL DEPOSITION OF DIELECTRIC SILICOL OXIDE BY PLASMA ENHANCED TEOS PROCESS", VMIC CONFERENCE, PI 411-415, 1989						
Examiner	<u> </u>			Date		

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>1</sup> Applicamt's unique citation designation number (optional). <sup>2</sup> See Kinds Codes of USPTO Patent Documents at <a href="www.uspto.gov">www.uspto.gov</a> or MPEP 901.04. <sup>2</sup> Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup> For Japanese patent documents, the indication of the year of the reign of the Emporen must preceded the serial number of the patent document. <sup>5</sup> Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST.16 if possible. <sup>6</sup> Applicant is to place a check mark here if English language Translation is statached.

<sup>1</sup> Applicant's unique citation designation number (optional). <sup>2</sup> Applicant is to place a check mark here if English language Translation is attached.

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